## Ionic Liquid and Amorphous Metal-Oxide Semiconductor Interactions:



# Towards a New Programmable Neuromorphic Platform



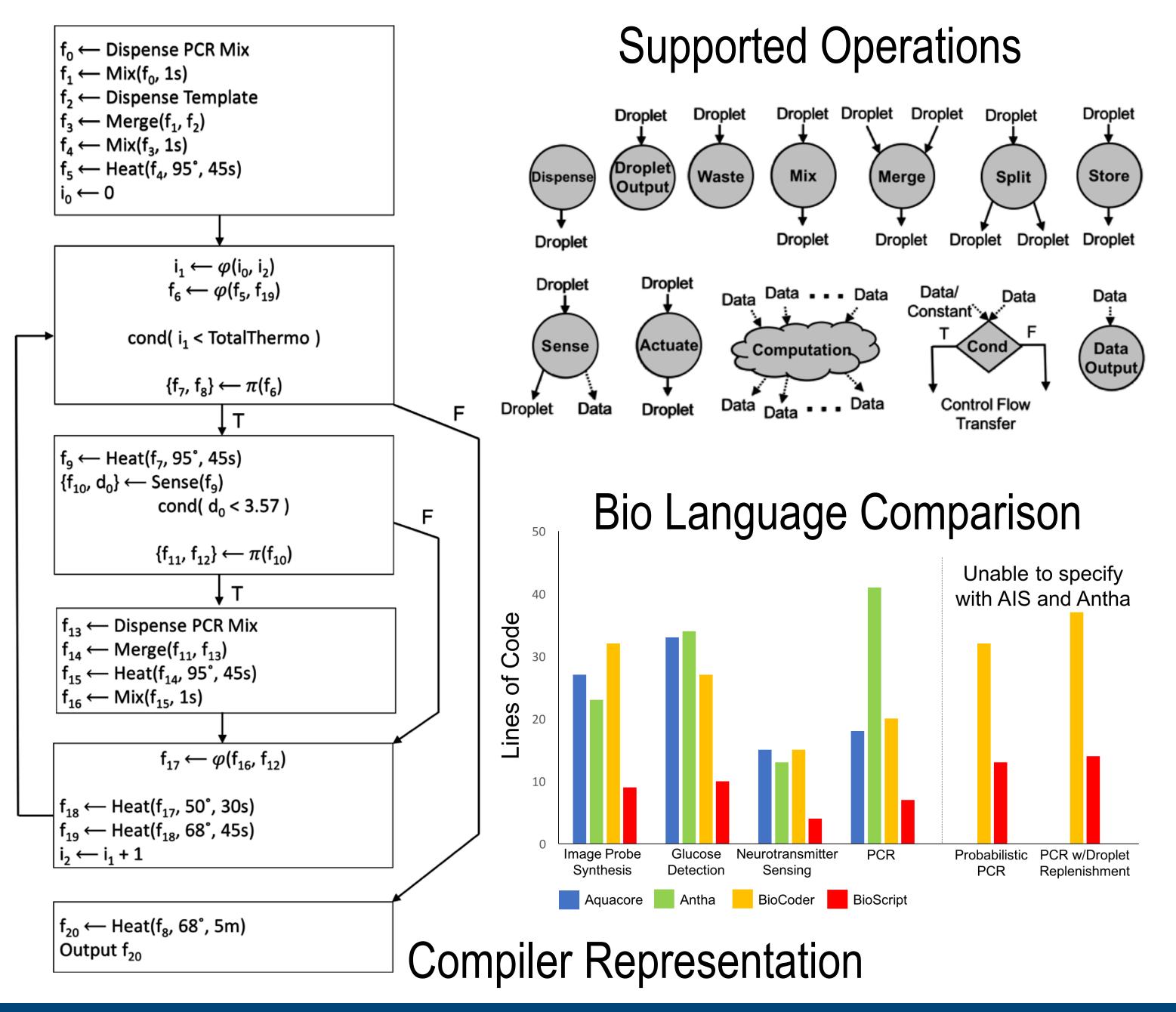
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1) University of California, Riverside 2) University of Tennessee 3) Center for Nanophase Materials Science, Oak Ridge National Laboratory

### **BioScript Programming Language for Digital Microfluidics**

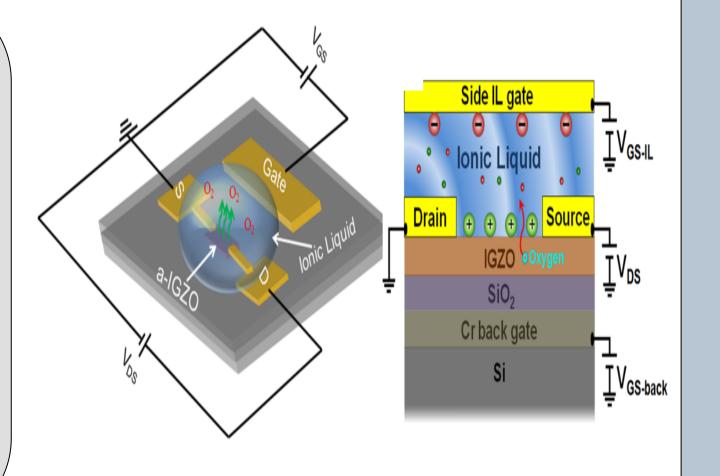
### Example Application: PCR with Droplet Replenishment

Heat PCRMix at 68C for 5min Save PCRMix



# Ionic Liquid Athermal Activation of Amorphous Metal-Oxide Semiconductors

Amorphous metal-oxide semiconductors offer the high carrier mobility and excellent large-area uniformity required for high performance, transparent, flexible electronic devices; however, a critical bottleneck to their widespread implementation is the need to activate these materials at high temperatures. We report highly controllable activation of amorphous IGZO semiconductor channels using ionic liquid gating at room temperature. Activation is controlled by electric field-induced oxygen migration across the ionic liquid-semiconductor interface.



Bias time (min)

a) Transfer characteristics of IL-gated TFT at 300K. +2.0 V IL gate bias. b)  $V_{th}$  as measured for the IL gate structure. c) Back gate measurements after IL bias time of 70 min. d) The back gate  $V_{th}$  as a function of IL bias time.

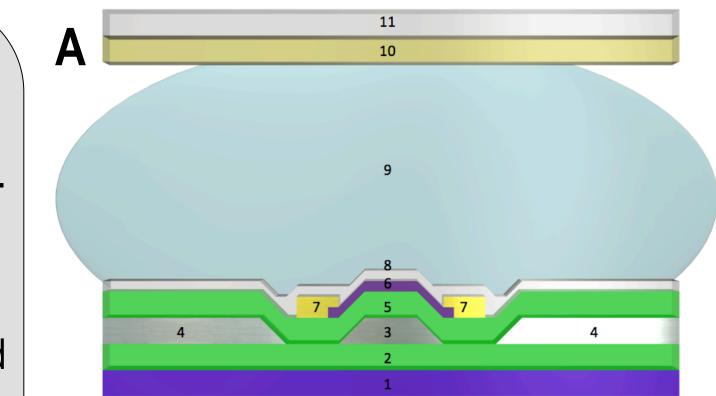
P.R. Pudasaini, J.H. Noh, A.T. Wong, O.S. Ovchinnikova, A.V. Haglund, S. Dai, T.Z. Ward, D. Mandrus, P.D. Rack, *Advanced Functional Materials*, **17**, 2820 (2016)

40 60 80

Bias time (min)

### Programmable Neuromorphic Device Schematic

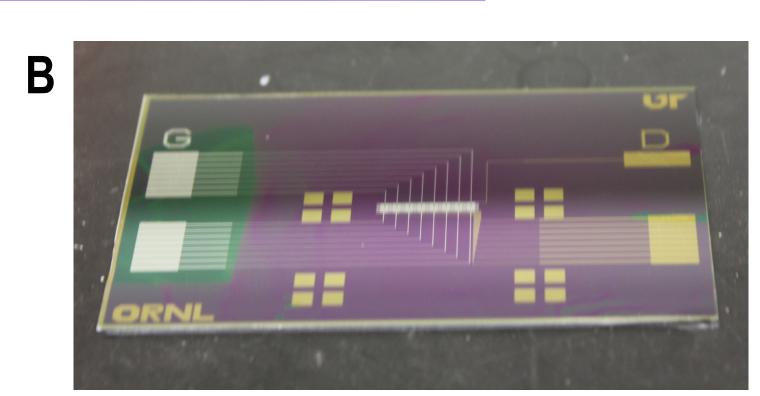
Neuromorphic computing attempts to model neuro - biological architectures using analog electronic signals. Using a hydrated Ionic liquid (BMIM-TFSI), we demonstrate control over an amorphous metal oxide transistor threshold voltage and on-current via H+ injection. Combining this with a pixelated electrowetting array results in a programmable neuromorphic platform which can be scaled to high pixel counts.



Si Wafer
Buffer: 500nm SiO<sub>2</sub>
Back Gate: 150nm Al
EW Pad: 150nm Al
G.I.: 100nm SiO<sub>2</sub>
Active: 50nm IGZO
S/D: 90nm Ti/Au
Hydrophobic: 400nm Teflon
lonic Liquid

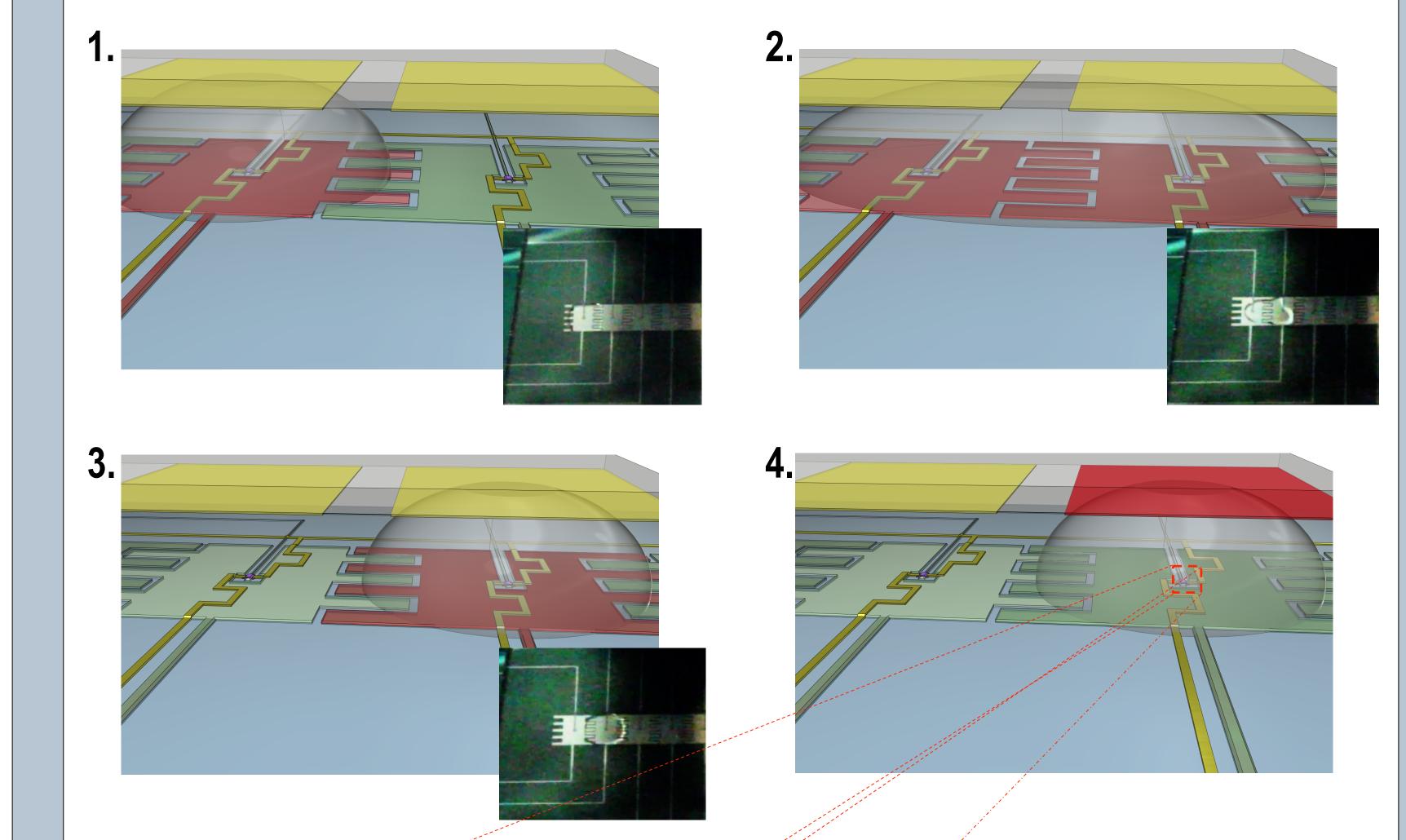
Top Gate: 100nm ITO

**Top Plate: Glass Slide** 

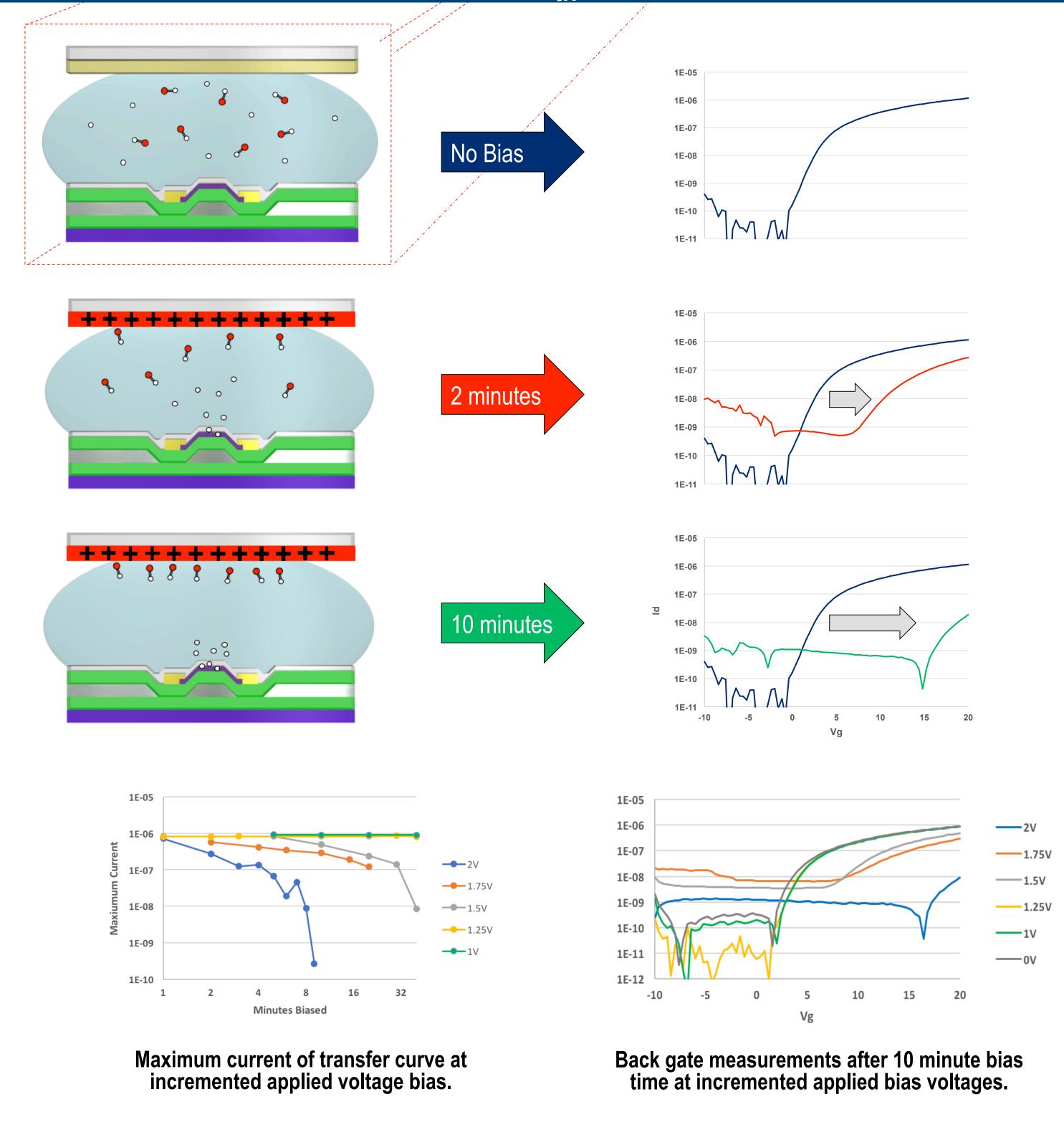


a) 2D Cross section of neuromorphic platform and b) photograph of fabricated device.

### **Electrowetting of Ionic Liquid**



### Modulation of Current and V<sub>th</sub> via Ionic Liquid Biasing



<u> —</u>0 min

V<sub>GS-IL</sub> (V)